

Applicant: Donald G. Parent  
For: SYSTEM FOR COATING INSULATIVE SUBSTRATES

ABSTRACT OF THE DISCLOSURE

5           A system for a method of applying a coating to an insulative substrate. The method  
includes applying a coating material to the insulative substrate by physical vapor  
deposition to a predetermined thickness at a rate and for a predetermined time which does  
not cause thermal damage to the insulative substrate. Then, before thermal damage can  
occur, moving the partially coated substrate proximate and active cooling station device  
10       to drive the temperature of the insulative substrate substantially down. The deposition  
and cooling steps are then repeated until the desired coating thickness is obtained to avoid  
thermal damage to the substrate.